

LPCVD	Tube 2	Material	Phosphorous Doped Poly Silicon Amorphous	
Uniformity:	Film Uniformity Variance < 2% across 4" wafer			
Gases	Flow Rate	Time(minutes)	Film Thickness(nm)	Deposition rate (nm/min)
Temperature	550 C	10	11.9	1.19
Comments:		20	25.5	1.28
		30	34.4	1.15
		40	45.6	1.14
		50	56.7	1.13
		60	67.4	1.12

